

## Poster Session 1

MAR 7 (Mon), 13:00-14:30

|         |  |       |    |
|---------|--|-------|----|
| P1-001A | <b>Behaviors of Pb Atom in the Multi-Micro Hollow Cathode Lamp Measured by Diode Laser Absorption Spectroscopy</b>   | ..... | 55 |
|         | <sup>1</sup> M. Inoue, <sup>1</sup> T. Ohta, <sup>1</sup> N. Takota, <sup>2</sup> M. Ito, <sup>3</sup> H. Kano, <sup>4</sup> K. Yamakawa, <sup>5</sup> M. Hori |       |    |
|         | <sup>1</sup> Wakayama University, Japan  |       |    |
|         | <sup>2</sup> Meijo University, Japan   |       |    |
|         | <sup>3</sup> NU EcoEngineering Co., LTD., Japan  |       |    |
|         | <sup>4</sup> Katagiri Engineering Co., LTD., Japan   |       |    |
|         | <sup>5</sup> Nagoya University, Japan  |       |    |
| P1-002A | <b>High Resolution Measurement of Silicon Substrate Temperature Using Frequency Domain Low Coherence Interferometer for Plasma Processing</b>                  | ..... | 55 |
|         | <sup>1</sup> T. Tsutsumi, <sup>1</sup> T. Ohta, <sup>2</sup> M. Ito, <sup>3</sup> M. Hori  |       |    |
|         | <sup>1</sup> Wakayama University, Japan  |       |    |
|         | <sup>2</sup> Meijo University, Japan   |       |    |
|         | <sup>3</sup> Nagoya University, Japan  |       |    |
| P1-003A | <b>Characteristics of Floating Metal Wire in Micro Plasma Using Spiral Coil</b>  | ..... | 56 |
|         | H. Asano, S. Kumagai, M. Sasaki  |       |    |
|         | Toyota Technological Institute, Japan  |       |    |
| P1-004A | <b>Three Dimensional Distribution of Atomic Radical in Nonequilibrium Atmospheric Pressure Plasma</b>  | ..... | 56 |
|         | <sup>1</sup> M. Kato, <sup>1,2</sup> K. Takeda, <sup>1</sup> K. Ishikawa, <sup>1</sup> H. Kondo, <sup>1,2</sup> M. Sekine, <sup>1,2</sup> M. Hori              |       |    |
|         | <sup>1</sup> Nagoya University, Japan  |       |    |
|         | <sup>2</sup> JST-CREST, Japan  |       |    |
| P1-005A | <b>Ignition Characteristics of Planer Micro-plasma Source Using Floating Sheet Electrode</b>   | ..... | 57 |
|         | Y. Yokoyama, H. Matsuyama, S. Kumagai, M. Sasaki   |       |    |
|         | Toyota Technological Institute, Japan  |       |    |
| P1-006A | <b>Infrared Spectroscopic Study on Reaction of Hydrogen Plasma with Si Surface</b>   | ..... | 57 |
|         | M. Shinohara, K. Hara, T. Kawakami, Y. Matsuda, H. Fujiyama  |       |    |
|         | Nagasaki University, Japan   |       |    |
| P1-007A | <b>Influence of Bio-Molecules Properties under Exposure to Low-Temperature Reactive Plasma</b>   | ..... | 58 |
|         | I. Motrescu, A. Ogino, M. Nagatsu  |       |    |
|         | Shizuoka University, Japan   |       |    |

|         |  |    |
|---------|--|----|
| P1-008A | <b>Development of 915 MHz UHF Waves Excited Surface-Wave Plasma Device for Large-area Plasma Processing</b>  | 58 |
|         | <sup>1</sup> K. Kunii, <sup>2</sup> A. Ogino, <sup>2</sup> M. Nagastu  |    |
|         | <sup>1</sup> Shizuoka University, Japan  |    |
|         | <sup>2</sup> Shizuoka University, Japan  |    |
| P1-009A | <b>Interaction of Pure Water-Ethanol Mixed Solution with Atmospheric Nitrogen Plasma Jet</b>   | 59 |
|         | A. Yamamoto, N. Oshima, T. Hara  |    |
|         | Toyota Technological Institute, Japan  |    |
| P1-010A | <b>Measurement of the Electron Temperature and Density of 60 Hz Nonequilibrium Atmospheric Pressure Plasma Jet by Laser Thomson Scattering</b>   | 59 |
|         | <sup>1</sup> F. Jia, <sup>2</sup> N. Sumi, <sup>1</sup> K. Ishikawa, <sup>3</sup> H. Kano, <sup>2</sup> H. Inui, <sup>2</sup> K. Takeda, <sup>2</sup> H. Kondo, <sup>2</sup> M. Sekine, <sup>2</sup> M. Hori |    |
|         | <sup>1</sup> Nagoya University, Japan  |    |
|         | <sup>2</sup> Nagoya University, Japan  |    |
|         | <sup>3</sup> NU Eco-Engineering Co., Ltd., Japan   |    |
| P1-011A | <b>Control of Multi-Hollow Microwave Plasma at High Pressure</b>   | 60 |
|         | <sup>1</sup> S. Ohta, <sup>1</sup> Iji Liang, <sup>1</sup> K. Kato, <sup>1</sup> K. Nakamura, <sup>2</sup> I. Ganachev, <sup>1</sup> H. Sugai  |    |
|         | <sup>1</sup> Chubu University, Japan   |    |
|         | <sup>2</sup> Shibaura Mechatronics Corp, Japan   |    |
| P1-012A | <b>Large Flow Atmospheric Microwave Plasma Apparatus (LAMP) of CO<sub>2</sub> Decomposition</b>  | 60 |
|         | S. Ikezawa, S. Parajulee, S. Sharma, A. Pandey   |    |
|         | Chubu University, Japan  |    |
| P1-013A | <b>Observation of Phenomena After Pulsed Laser Irradiation to Solid with Optical Wave Microphone</b>   | 61 |
|         | <sup>1</sup> F. Mitsugi, <sup>1</sup> T. Ikegami, <sup>2</sup> T. Nakamiya, <sup>2</sup> Y. Sonoda   |    |
|         | <sup>1</sup> Kumamoto University, Japan  |    |
|         | <sup>2</sup> Tokai University, Japan   |    |
| P1-014A | <b>Atmospheric Pressure Discharge Device for Biomedical Application</b>  | 61 |
|         | <sup>1</sup> S. Kitazaki, <sup>1</sup> K. Koga, <sup>1</sup> G. Uchida, <sup>1</sup> M. Shiratani, <sup>2</sup> N. Hayashi   |    |
|         | <sup>1</sup> Kyushu University, Japan  |    |
|         | <sup>2</sup> Saga University, Japan  |    |

|         |  |    |
|---------|--|----|
| P1-015A | <b>Damage Analysis of Plasma-etched n-GaN Crystal Surface by N-K Absorption Spectroscopy</b>   | 62 |
|         | <sup>1</sup> M. Niibe, <sup>1</sup> T. Kotaka, <sup>2</sup> R. Kawakami, <sup>2</sup> T. Inaoka, <sup>2</sup> K. Tominaga, <sup>3</sup> T. Mukai                                   |    |
|         | <sup>1</sup> University of Hyogo, Japan  |    |
|         | <sup>2</sup> The University of Tokushima, Japan  |    |
|         | <sup>3</sup> Nichia Corporation, Japan   |    |
| P1-016A | <b>Miniaturization of Plane-Type Microwave Resonator Probe</b>   | 62 |
|         | E. Kumazaki, K. Nakamura, H. Sugai   |    |
|         | Chubu University, Japan  |    |
| P1-017A | <b>Flowing Liquid Treatment by Microwave Plasma under Reduced Pressure Condition</b>   | 63 |
|         | <sup>1</sup> K. Kanetake, <sup>2</sup> T. Ishijima, <sup>1,2</sup> H. Toyoda   |    |
|         | <sup>1</sup> Nagoya University, Japan  |    |
|         | <sup>2</sup> Nagoya University, Japan  |    |
| P1-018A | <b>Effects of Argon Flow Rate on the Atomic Emission Process of Cu Solution in Atmospheric Pressure Plasma</b>   | 63 |
|         | <sup>1</sup> J. Kularatne, <sup>2</sup> H. Kano, <sup>3</sup> M. Ito, <sup>4</sup> T. Ohta, <sup>1</sup> K. Takeda, <sup>1</sup> H. Kondo, <sup>1</sup> M. Hori                    |    |
|         | <sup>1</sup> Nagoya University, Japan  |    |
|         | <sup>2</sup> NU Eco Engineering, Japan   |    |
|         | <sup>3</sup> Meijo University, Japan   |    |
|         | <sup>4</sup> Wakayama University, Japan  |    |
| P1-019A | <b>Pulsed Power Microplasma Diagnostics for Glass' Surface Treatment</b>   | 64 |
|         | M. Blajan, A. Umeda, K. Shimizu  |    |
|         | Shizuoka University, Japan   |    |
| P1-020A | <b>Optical Study on the Mechanisms of Gliding Arc Discharge</b>  | 64 |
|         | <sup>1</sup> H. Kawasaki, <sup>2</sup> I. Muramoto, <sup>2</sup> S. Aoqui, <sup>3</sup> F. Mitsugi, <sup>1</sup> T. Ohshima, <sup>1</sup> Y. Yagyu, <sup>1</sup> Y. Suda           |    |
|         | <sup>1</sup> Sasebo National College of Technology, Japan  |    |
|         | <sup>2</sup> Sojo University, Japan  |    |
|         | <sup>3</sup> Kumamoto University, Japan  |    |
| P1-021A | <b>RF Plasma Transition Caused by Gas Puffing and/or DC Biasing using Multiturn Internal Antenna</b>   | 65 |
|         | <sup>1</sup> T. Yamauchi, <sup>1</sup> S. Kobayashi, <sup>2</sup> H. Sugibayashi, <sup>3</sup> T. Tachibana, <sup>4</sup> S. Naitoh, <sup>2</sup> Y. Kanno, <sup>1</sup> T. Hiruta |    |
|         | <sup>1</sup> Japan Atomic Energy Agency, Japan   |    |
|         | <sup>2</sup> Advanced Institute of Industrial Technology, Japan  |    |
|         | <sup>3</sup> Ibaraki National College of Technology, Japan   |    |
|         | <sup>4</sup> Tokyo University, Japan   |    |

|         |  |    |
|---------|--|----|
| P1-022A | <b>Properties of High Pressure RF He/CH<sub>4</sub> Discharges</b>   | 65 |
|         | S. Kanzaki, A. Oda, T. Kimura<br>Nagoya Institute of Technology, Japan   |    |
| P1-023A | <b>Optimal O<sub>3</sub> Production in Health Regulation Used Corona Discharge</b>   | 66 |
|         | S. Chun, S. Joa, J. Kim, I. Kang, H. Lee<br>Jeju National University, Korea  |    |
| P1-024A | <b>Effects of Non-Thermal Plasma Technology on Growth and Yield of Berseem Crop and Traits Some Biochemical Analysis</b>   | 66 |
|         | <sup>1</sup> G. M. El-Aragi, <sup>2</sup> G. Abd El-Daeem, <sup>3</sup> E. Zayed, <sup>3</sup> M. Tarrad<br><sup>1</sup> Egyptian Atomic Energy, Egypt<br><sup>2</sup> Egyptian Atomic Energy, Egypt<br><sup>3</sup> ARC, FCRCI, FCRD, Egypt                       |    |
| P1-025A | <b>Effects of Corona Discharge Treatment on Some Properties of Wool Fabrics</b>  | 67 |
|         | <sup>1</sup> M. Mirjalili, <sup>2</sup> S. Nasirian<br><sup>1</sup> Islamic Azad University, Iran<br><sup>2</sup> Islamic Azad University, Yazd Branch, Iran   |    |
| P1-026A | <b>Development of the DC-RF Hybrid Plasma System and its Application to the Etching and Cleaning of Silicon</b>  | 67 |
|         | J. Kim, S. Chun, S. Joa, I. Kang, H. Lee<br>Jeju National University, Korea  |    |
| P1-027B | <b>Radial Growth of GaN Nanowires by NaCl-assisted Plasma-enhanced Chemical Vapor Deposition</b>   | 68 |
|         | W. Hou, T. Wu, W. Tang, J. Tsai, W. Tsai, F. Hong<br>National Cheng Kung University, Taiwan  |    |
| P1-028B | <b>Effect of Nitrogen Source on Doping Properties of GaN:Eu Grown by MBE</b>   | 68 |
|         | <sup>1</sup> T. Suwa, <sup>2</sup> Y. Takagi, <sup>1</sup> H. Sekiguchi, <sup>1</sup> H. Okada, <sup>1</sup> A. Wakahara<br><sup>1</sup> Toyohashi University of Technology, Japan<br><sup>2</sup> Hamamatsu Photonics K. K., Japan                                |    |
| P1-029B | <b>GaN (0001)/Al<sub>2</sub>O<sub>3</sub> Epitaxial Films, Synthesized By Reactive High Power Impulse Magnetron Sputter Deposition using Ga as a Liquid Target</b>   | 69 |
|         | <sup>1</sup> M. Junaid, <sup>1</sup> C. Hsio, <sup>1</sup> J. Palisaitis, <sup>1</sup> D. Lundin, <sup>2</sup> W. Lai, <sup>2</sup> L. Chen, <sup>1</sup> J. Birch<br><sup>1</sup> Linkoping University, Sweden<br><sup>2</sup> National Taiwan University, Taiwan |    |

|         |  |    |
|---------|--|----|
| P1-030B | <b>Intentional Carbon Doping to GaN by MOVPE</b>   | 69 |
|         | <sup>1</sup> K. Yamashita, <sup>1</sup> T. Sugiyama, <sup>1</sup> Y. Honda, <sup>1</sup> M. Yamaguchi, <sup>1</sup> H. Amano, <sup>2</sup> N. Sawaki |    |
|         | <sup>1</sup> Nagoya University, Japan  |    |
|         | <sup>2</sup> Aichi Institute of Technology, Japan  |    |
| P1-031B | <b>Effect of Growth Temperature on Structural Quality of InAlN Layer Lattice-Matched to GaN Grown by MOCVD</b>                                       | 70 |
|         | J. Ichikawa, Y. Sakai, Z. Chen, K. Fujita, T. Egawa  |    |
|         | Nagoya Institute of Technology, Japan  |    |
| P1-032B | <b>High Power GaN-Based LEDs with Nano-Structured Ga-Doped ZnO (GZO) Transparent Conductive Layer (TCL)</b>  | 70 |
|         | G. Wang, B. Fan, W. Jia, K. Tong, R. Mond, Y. Liu, H. Jiang  |    |
|         | Sun Yat-Sen University, China  |    |
| P1-033B | <b>GaN Single Crystals by Solution Growth under Atomic Nitrogen and Hydrogen Plasma Mixture</b>  | 71 |
|         | <sup>1</sup> T. Ozawa, <sup>1</sup> N. Harada, <sup>1</sup> M. Dohi, <sup>2</sup> Y. Hayakawa  |    |
|         | <sup>1</sup> Shizuoka Institute of Science and Technology, Japan   |    |
|         | <sup>2</sup> Shizuoka University, Japan  |    |
| P1-034B | <b>Characteristics of a-plane InGaN/GaN Multiple Quantum Well Layers and LEDs Grown on r-plane Sapphire</b>  | 71 |
|         | <sup>1,3</sup> K. Song, <sup>1</sup> J. Kim, <sup>1</sup> C. Shin, <sup>1</sup> C. Ko, <sup>2</sup> S. Hwang, <sup>3</sup> D. Yoon                   |    |
|         | <sup>1</sup> Korea Advanced Nano Fab Center, Korea   |    |
|         | <sup>2</sup> Korea Electronics Technology Institute, Korea   |    |
|         | <sup>3</sup> Sungkyunkwan University, Korea  |    |
| P1-035B | <b>Growth Mechanism of Selective Growth of GaN by RF-MBE</b>   | 72 |
|         | Y. Nagae, Y. Osawa, T. Iwatsuki, Y. Shirai, S. Naritsuka, T. Maruyama  |    |
|         | Meijo University, Japan  |    |
| P1-036B | <b>Design and Fabrication of AlN/GaN Heterostructures for Intersubband Technology</b>  | 72 |
|         | T. Andersson, K. Berland, R. Farivar, F. Falth, P. Hyldgaard, T. Ive, A. Larsson, M. Stattin, S. Wang  |    |
|         | Chalmers, Sweden   |    |
| P1-037B | <b>Sc<sub>x</sub>Al<sub>x</sub>N(0001) - Further Investigations of Electrical Properties of Sputter Deposited Thin Films</b>                         | 73 |
|         | G. Wingqvist, A. Zukauskaite, F. Tasnadi, J. Birch, L. Hultman   |    |
|         | Linkoping university, Sweden   |    |

|         |   |    |
|---------|---|----|
| P1-038B | <b>Vertical Schottky Device for GaN on Si using 3C-SiC intermediate layers</b>  | 73 |
|         | <sup>1</sup> Y. Abe, <sup>1</sup> J. Komiyama, <sup>2</sup> A. Watanabe, <sup>1</sup> S. Suzuki, <sup>1</sup> H. Nakanishi, <sup>2</sup> T. Egawa   |    |
|         | <sup>1</sup> Covalent Materials Corporation, Japan  |    |
|         | <sup>2</sup> Nagoya Institute of Technology, Japan  |    |
| P1-039B | <b>FTIR Spectra and LVMs in a Carbon Doped (1-101)GaN Grown on a (001)Si Substrate by MOVPE</b>   | 74 |
|         | <sup>1</sup> N. Sawaki, <sup>1</sup> K. Hagiwara, <sup>1</sup> M. Amano, <sup>1</sup> R. Katayama, <sup>2</sup> Y. Honda, <sup>2</sup> T. Hikosaka, <sup>2</sup> T. Tanikawa, <sup>2</sup> N. Koide, <sup>2</sup> M. Yamaguchi, <sup>2</sup> H. Amano |    |
|         | <sup>1</sup> Aichi Institute of Technology, Japan   |    |
|         | <sup>2</sup> Nagoya University, Japan   |    |
| P1-040B | <b>Investigation of SiO<sub>2</sub>/p-GaN Interfaces by Capacitance and Conductance Analysis</b>  | 74 |
|         | T. Kubo, J. Freedzman, Y. Iwata, T. Egawa   |    |
|         | Nagoya Institute of Technology, Japan   |    |
| P1-041B | <b>Crystallographic Wet Chemical Etching of Semi-polar GaN(1122) and Non-polar GaN (1120)</b>   | 75 |
|         | <sup>1</sup> D. Lee, <sup>1</sup> J. Kim, <sup>2</sup> S. Lee, <sup>3</sup> K. Song, <sup>1</sup> J. Lee  |    |
|         | <sup>1</sup> Sunchon National University, Korea   |    |
|         | <sup>2</sup> Korea Polytechnic University, Korea  |    |
|         | <sup>3</sup> Korea Advanced Nano Fab Center, Korea  |    |
| P1-042C | <b>Electrical Properties of Amorphous Carbon Thin Films Deposited by Aerosol-Assisted Thermal CVD</b>   | 75 |
|         | A. Fadzilah, M. Rusop   |    |
|         | Universiti Teknologi MARA, Malaysia   |    |
| P1-043C | <b>Thickness Effect on Nanocomposite MEH-PPV:_CNT:TiO<sub>2</sub> Thin Film in Organic Solar Cell</b>   | 76 |
|         | M. Mahmood, P. Sarah Mohamad Saad   |    |
|         | Universiti Teknologi MARA, Malaysia   |    |
| P1-044C | <b>Fabrication and Electrical Conductivity Measurements of Single Carbon Nanowall Bridging between Metal Electrodes</b>   | 76 |
|         | <sup>1</sup> T. Kanda, <sup>2</sup> K. Yamakawa, <sup>1</sup> H. Kondo, <sup>3</sup> M. Hiramatsu, <sup>1</sup> M. Sekine, <sup>1</sup> M. Hori   |    |
|         | <sup>1</sup> Nagoya University, Japan   |    |
|         | <sup>2</sup> Katagiri Engineering Co., Ltd., Japan  |    |
|         | <sup>3</sup> Meijo University, Japan  |    |

|         |  |    |
|---------|--|----|
| P1-045C | <b>Synthesis of Platinum Nanoparticles on Carbon Nanowall Surface by Supercritical Fluid Chemical Deposition</b>   | 77 |
|         | <sup>1</sup> S. Mitsuguchi, <sup>3</sup> H. Kano, <sup>1</sup> M. Hiramatsu, <sup>2</sup> H. Kondo, <sup>2</sup> M. Sekine, <sup>2</sup> M. Hori                           |    |
|         | <sup>1</sup> Meijo University, Japan   |    |
|         | <sup>2</sup> Nagoya University, Japan  |    |
|         | <sup>3</sup> NU Eco Engineering, Co., LTD., Japan  |    |
| P1-046C | <b>Charateristics of Carbon Nanoflakes Depositing on Carbon Cloth with NiO Overlayer for Electric Double Layer Capacitor Application</b>                                   | 77 |
|         | <sup>1</sup> H. Chang, <sup>1</sup> H. Chang, <sup>1,2</sup> K. Lee, <sup>2</sup> W. Shih  |    |
|         | <sup>1</sup> National Taiwan University of Science And Technology, Taiwan  |    |
|         | <sup>2</sup> Tatung University, Taiwan   |    |
| P1-047C | <b>STS Observation of Local Density of States on Growth Surfaces at an Initial Stage of Carbon Nanowall Synthesis</b>  | 78 |
|         | <sup>1</sup> K. Yasuda, <sup>1</sup> H. Kondo, <sup>2</sup> M. Hiramatsu, <sup>1</sup> M. Sekine, <sup>1</sup> M. Hori   |    |
|         | <sup>1</sup> Nagoya University, Japan  |    |
|         | <sup>2</sup> Meijo University, Japan   |    |
| P1-048C | <b>Effects of Substrate Temperatures on Crystallographic Changes of Carbon Nanowalls Induced by Radical Irradiation</b>  | 78 |
|         | <sup>1</sup> H. Shimoeda, <sup>1</sup> H. Kondo, <sup>1</sup> K. Takeda, <sup>1</sup> K. Ishikawa, <sup>2</sup> M. Hiramatsu, <sup>1</sup> M. Sekine, <sup>1</sup> M. Hori |    |
|         | <sup>1</sup> Nagoya University, Japan  |    |
|         | <sup>2</sup> Meijo University, Japan   |    |
| P1-049C | <b>Determination of C Atom Density in Microwave Plasma with Carbon-Containing Gases by Vacuum Ultraviolet Absorption Spectroscopy</b>                                      | 79 |
|         | <sup>1</sup> K. Murata, <sup>1</sup> M. Naito, <sup>1</sup> M. Hiramatsu, <sup>2</sup> S. Takashima, <sup>3</sup> H. Kondo, <sup>3</sup> M. Hori                           |    |
|         | <sup>1</sup> Meijo University, Japan   |    |
|         | <sup>2</sup> Plasma Center for Industrial Applications, Japan  |    |
|         | <sup>3</sup> Nagoya University, Japan  |    |
| P1-050C | <b>Area-selective Nucleation of Carbon Nanowalls by Using Catalyzed Substrate</b>  | 79 |
|         | <sup>1</sup> Y. Nihashi, <sup>1</sup> M. Hiramatsu, <sup>2</sup> H. Kondo, <sup>2</sup> M. Hori  |    |
|         | <sup>1</sup> Meijo University, Japan   |    |
|         | <sup>2</sup> Nagoya University, Japan  |    |
| P1-051C | <b>Carbon Electrode Having Large Capacitance Prepared by Pulsed DC Plasma CVD</b>  | 80 |
|         | M. Matsushima, G. Kalita, K. Wakita, H. Uchida, M. Noda, M. Umeno  |    |
|         | Chubu University, Japan  |    |

|         |   |       |    |
|---------|---|-------|----|
| P1-052C | <b>The Formation of MWCNTs on Carbon Substrates via Metal-catalyst-free Chemical Vapor Deposition</b>   | ..... | 80 |
|         | <sup>1</sup> J. Lin, <sup>1</sup> Z. Zeng, <sup>2</sup> H. Ma, <sup>2</sup> H. Chen   |       |    |
|         | <sup>1</sup> National University of Tainan, Taiwan  |       |    |
|         | <sup>2</sup> National Sun Yat-sen University, Taiwan  |       |    |
| P1-053C | <b>High-Speed Synthesis of Nano-Graphene by In-liquid Plasma in Alcohol</b>   | ..... | 81 |
|         | <sup>1</sup> T. Hagino, <sup>2</sup> H. Kano, <sup>1</sup> K. Ishikawa, <sup>1</sup> K. Takeda, <sup>1</sup> H. Kondo, <sup>1</sup> M. Sekine, <sup>1</sup> M. Hori |       |    |
|         | <sup>1</sup> Nagoya University, Japan   |       |    |
|         | <sup>2</sup> NU Eco Engineering, Japan  |       |    |
| P1-054C | <b>Electric Property of CNT/SiC Interface formed by Surface Deposition of SiC</b>   | ..... | 81 |
|         | <sup>1</sup> S. Sakakibara, <sup>1</sup> S. Naritsuka, <sup>2</sup> H. Yamane, <sup>2</sup> E. Shigemasa, <sup>2</sup> N. Kosugi, <sup>1</sup> T. Maruyama          |       |    |
|         | <sup>1</sup> Meijo University, Japan  |       |    |
|         | <sup>2</sup> Institute for Molecular Science, Japan   |       |    |
| P1-055C | <b>Affection of Hydrophilic and Hydrophobic of Carbon Nanowalls Using Plasma Surface Treatment</b>  | ..... | 82 |
|         | <sup>1</sup> H. Watanabe, <sup>1</sup> K. Takada, <sup>1</sup> H. Kondo, <sup>2</sup> M. Hiramatsu, <sup>1</sup> M. Hori  |       |    |
|         | <sup>1</sup> Nagoya University, Japan   |       |    |
|         | <sup>2</sup> Meijo University, Japan  |       |    |
| P1-056C | <b>Epitaxial Graphene on Si (111) Substrate by Annealing Carbonized Silicon</b>   | ..... | 82 |
|         | H. Aryal, K. Fujita, K. Banno, T. Egawa   |       |    |
|         | Nagoya Institute of Technology, Japan   |       |    |
| P1-057C | <b>Ion Storage Properties of Inner, Outer, Unwrapped, and Chemically Modified Surface of Single Walled Carbon Nanotubes</b>   | ..... | 83 |
|         | A. Alzubaidi, T. Inoue, T. Matsushita, S. Kawasaki  |       |    |
|         | Nagoya Institute of Technology, Japan   |       |    |
| P1-058C | <b>Carbon-Coated Co Nanoparticles Synthesized by Pulsed Plasma in Liquid</b>  | ..... | 83 |
|         | <sup>1</sup> Z. Abdullaeva, <sup>2</sup> E. Omurzak, <sup>3</sup> C. Iwamoto, <sup>4</sup> T. Mashimo, <sup>5</sup> S. Sulaimankulova                               |       |    |
|         | <sup>1</sup> Kumamoto University, Japan   |       |    |
|         | <sup>2</sup> Kumamoto University, Japan   |       |    |
|         | <sup>3</sup> Kumamoto University, Japan   |       |    |
|         | <sup>4</sup> Kumamoto University, Japan   |       |    |
|         | <sup>5</sup> Institute of Chemistry and Chemical Technology, Kyrgyz   |       |    |

|         |   |       |    |
|---------|---|-------|----|
| P1-059C | <b>Synthesis of Carbon Nanoflakes by Radio-Frequency Sputtering on Stainless Steel for Field Emission Application</b>   | ..... | 84 |
|         | <sup>1</sup> W. Shih, <sup>1</sup> J. Jeng, <sup>1</sup> H. Chang, <sup>2</sup> J. Lo   |       |    |
|         | <sup>1</sup> Tatung University, Taiwan  |       |    |
|         | <sup>2</sup> Tatung Company, Taiwan   |       |    |
| P1-060C | <b>Local Area Deposition of Carbon Nano-materials by an Atmospheric-Pressure Microplasma</b>  | ..... | 84 |
|         | <sup>1</sup> H. Yoshiki, <sup>1</sup> J. Sato, <sup>2</sup> Y. Sugioka, <sup>2</sup> Y. Suda  |       |    |
|         | <sup>1</sup> Tsuruoka National College of Technology, Japan   |       |    |
|         | <sup>2</sup> Toyohashi University of Technology, Japan  |       |    |
| P1-061C | <b>Preparation of MAX-Phase Containing Ti-Si-C Thin Films by Magnetron Sputtering Using Elemental Targets</b>   | ..... | 85 |
|         | T. Sonoda, S. Nakao, M. Ikeyama   |       |    |
|         | National Institute of Advance Industrial Science and Technology (AIST), Japan   |       |    |
| P1-062C | <b>Electrocatalytic Activity of Chemical and Plasma Modified Single-Walled Carbon Nanotube(SWCNT) Surface</b>   | ..... | 85 |
|         | J. Kim, N. Min, J. Jin, E. Park   |       |    |
|         | Korea University, Korea   |       |    |
| P1-063C | <b>Effects of Irradiation Energy on the Synthesis of High Yield Nitrogen Atom Endohedral Fullerenes in RF Plasmas</b>   | ..... | 86 |
|         | S. Cho, T. Kaneko, R. Hatakeyama  |       |    |
|         | Tohoku University, Japan  |       |    |
| P1-064C | <b>Effect of N<sub>2</sub>O Plasma Post-Treatment on the Performance Improvement of Field Emission Properties for the Multi-Wall Carbon Nanotubes</b>         | ..... | 86 |
|         | <sup>1</sup> C. Fan, <sup>1</sup> H. Lai, <sup>1</sup> T. Huang, <sup>2</sup> W. Wu   |       |    |
|         | <sup>1</sup> National Taiwan University of Science and Technology, Taiwan   |       |    |
|         | <sup>2</sup> National Nano Device Laboratories, Taiwan  |       |    |
| P1-065C | <b>Carbon Nanotubes Synthesis in Liquid Xylene by Low-frequency Pulsed Arc Discharge Using Copper Electrodes: An Effect of Current Waveform of Pulsed Arc</b> | ..... | 87 |
|         | T. Kizu, S. Aikawa, K. Takekoshi, E. Nishikawa  |       |    |
|         | Tokyo University of Science, Japan  |       |    |

|         |   |       |    |
|---------|---|-------|----|
| P1-066C | <b>Fabrication of Aligned Carbon Nanotube Films using Microwave Plasma-Enhanced CVD</b>   | ..... | 87 |
|         | <sup>1</sup> M. Naito, <sup>1</sup> K. Murata, <sup>1</sup> M. Hiramatsu, <sup>2</sup> M. Hori  |       |    |
|         | <sup>1</sup> Meijo University, Japan  |       |    |
|         | <sup>2</sup> Nagoya University, Japan   |       |    |
| P1-067C | <b>Fabrication and Characterization of Conical Nanocarbon Structures on Polymer Substrates for Transparent and Flexible Field Emission Displays</b>                 | ..... | 88 |
|         | D. Ghosh, P. Ghosh, S. Satoh, M. Kawagishi, A. Hayashi, Y. Hayashi, M. Tanemura   |       |    |
|         | Nagoya Institute of Technology, Japan   |       |    |
| P1-068C | <b>Electrical and Optical Properties of Nitrogen Doped Diamond-like Carbon Films Prepared by a Bipolar-Type Plasma based Ion Implantation</b>                       | ..... | 88 |
|         | <sup>1</sup> S. Nakao, <sup>2</sup> T. Soga, <sup>2</sup> T. Asada, <sup>2</sup> N. Kishi   |       |    |
|         | <sup>1</sup> AIST-Chubu, Japan  |       |    |
|         | <sup>2</sup> Nagoya Institute of Technology, Japan  |       |    |
| P1-069C | <b>Basic Consideration of Mixture Ratio of Electrolyte and Platinum Loaded Carbon for Proton Exchange Membrane Fuel Cell</b>  | ..... | 89 |
|         | Y. Suenaga, Y. Sakaguchi, Y. Urakawa, D. Tashima, M. Otsubo   |       |    |
|         | University of Miyazaki, Japan   |       |    |
| P1-070C | <b>Pt Coating on Carbon Nanotwist Field Emitter and its Upright Position</b>  | ..... | 89 |
|         | <sup>1</sup> Y. Sugioka, <sup>1</sup> Y. Suda, <sup>1</sup> H. Tanoue, <sup>1</sup> H. Takikawa, <sup>2</sup> H. Ue, <sup>3</sup> Y. Umeda, <sup>4</sup> K. Shimizu |       |    |
|         | <sup>1</sup> Toyohashi University of Technology, Japan  |       |    |
|         | <sup>2</sup> Tokai Carbon Co., Ltd., Japan  |       |    |
|         | <sup>3</sup> Toho Gas Co., Ltd., Japan  |       |    |
|         | <sup>4</sup> Shonan Plastic Mfg. Co., Ltd., Japan   |       |    |
| P1-071C | <b>Carbon Nanotube Growth on ZnO Substrate Surfaces using Alcohol Gas Source Method in High Vacuum</b>  | ..... | 90 |
|         | T. Iokawa, S. Naritsuka, T. Maruyama  |       |    |
|         | Meijo University, Japan   |       |    |
| P1-072C | <b>Simulation for Hydrogen Retention in Carbon Materials</b>  | ..... | 90 |
|         | <sup>1</sup> S. Saito, <sup>2</sup> A. Takayama, <sup>2</sup> A. Ito, <sup>12</sup> H. Nakamura   |       |    |
|         | <sup>1</sup> Nagoya University, Japan   |       |    |
|         | <sup>2</sup> National Institute for Fusion Science, Japan   |       |    |

|         |   |       |    |
|---------|---|-------|----|
| P1-073C | <b>Synthesis of Aligned Carbon Nanotube by Direct Current Plasma Enhanced Chemical Vapor Deposition (PECVD) System</b>        | ..... | 91 |
|         | M. Vahidi, A. Afzali, F. Ahmad-Zadeh, A. Rashidi  |       |    |
|         | Research Institute of Petroleum Industry (R.I.P.I), Iran  |       |    |
| P1-074C | <b>Low-temperature Growth of Carbon Nanosheets by Microwave Plasma Chemical Vapor Deposition</b>                              | ..... | 91 |
|         | <sup>1</sup> Z. Wang, <sup>2</sup> M. Shoji, <sup>2</sup> H. Ogata  |       |    |
|         | <sup>2</sup> Hosei University, Japan  |       |    |
|         | <sup>2</sup> Hosei University, Japan  |       |    |
| P1-075C | <b>Measurement of Structure-Changed Layer of Hydrogen-free DLC after Sliding in Base Oil by Using Reflection Spectroscopy</b> | ..... | 92 |
|         | <sup>1</sup> Y. Inagaki, <sup>1</sup> H. Kousaka, <sup>1</sup> N. Umehara, <sup>2</sup> Y. Mabuchi, <sup>2</sup> T. Higuchi   |       |    |
|         | <sup>1</sup> Nagoya University, Japan   |       |    |
|         | <sup>2</sup> NISSAN Motor Co., Ltd, Japan   |       |    |
| P1-076C | <b>Alignment of Dispersed Graphene Sheets by Dielectrophoretic Force</b>  | ..... | 92 |
|         | J. Ahn, J. Lee, J. Kim  |       |    |
|         | Korea University, Korea   |       |    |
| P1-077C | <b>Growth Control of Carbon Nanotubes by Low Pressure Alcohol Catalytic Chemical Vapor Deposition</b>                         | ..... | 93 |
|         | D. Sawaguchi, H. Sato, K. Hata, H. Miyake, K. Iida, K. Hiramatsu  |       |    |
|         | Mie University, Japan   |       |    |
| P1-078C | <b>A DFT and MD Study on Interaction of Water Molecules with Graphene</b>   | ..... | 93 |
|         | S. Abe, Y. Nagoya, F. Watari, H. Tachikawa  |       |    |
|         | Hokkaido University, Japan  |       |    |

withdrawn

P1-081C **Magnetic Property of FePt Nanoparticles Encapsulated in Multi-Walled Carbon Natotubes Grown by Thermal Chemical Vapor Deposition**

95

<sup>1</sup>T. Kaneko, <sup>1</sup>Y. Fujiwara, <sup>1</sup>H. Sato, <sup>1</sup>K. Maeda, <sup>2</sup>T. Kato, <sup>2</sup>S. Iwata, <sup>1</sup>K. Hata, <sup>1</sup>T. Kobayashi

<sup>1</sup>Mie University, Japan

<sup>2</sup>Nagoya University, Japan

- P1-082A-LN **Plasma Damage Diagnosis of the Gate Dielectric Using the Edge Type Sensor**  
<sup>1,2</sup>Y. Jung, <sup>1</sup>H. Kim, <sup>2</sup>Y. Roh  
<sup>1</sup>Samsung Electronics, Korea  
<sup>2</sup>Sungkyunkwan University, Korea
- P1-083A-LN **Plasma Ultra Violet Damage Evaluation of the Dielectric Using the Basic Plannar Type Sensor**  
<sup>1,2</sup>K. Kim, <sup>1</sup>Y. Roh,  
<sup>1</sup>Samsung Electronics, Korea  
<sup>2</sup>Sungkyunkwan University, Korea
- P1-084A-LN **Optimization of the Concentration of Nitride in the ONO Structure by the Plasma Nitridation and its Effect on the Yield**  
<sup>1</sup>S. Choi, <sup>1</sup>H. Kim, <sup>1</sup>Y. Roh  
<sup>1</sup>Sungkyunkwan University, Korea
- P1-085A-LN **Comparative Study of Inhibitory Action and of Glidarc Plasma Processing of Carbon Steel C75**  
<sup>1</sup>A. Addou, <sup>1,2</sup>N. Ghali, <sup>2</sup>B. Mutel  
<sup>1</sup>Mostaganem University, Algeria  
<sup>2</sup>Lille University, France
- P1-086A-LN **Plasma Diagnostics for N<sub>2</sub>-H<sub>2</sub> Plasmas Using a Quartz Sensor**  
<sup>1</sup>A. Suzuki, <sup>2</sup>S. Asahina  
<sup>1</sup>National Institute of Advanced Industrial Science and Technology AIST, Japan  
<sup>2</sup>Shimane Institute for Industrial Technology, Japan
- P1-087A-LN **Floating Harminics Analysis Method in Non-Maxweelian Plasmas**  
<sup>1</sup>C. Chung, <sup>1</sup>J. Bang  
<sup>1</sup>Dept. of Electrical Engineering, Hanyang University, Korea
- P1-088A-LN **Application of Inductively Coupled Plasma Spectrometry for the Analysis of Reach Behavior of LiMnO<sub>4</sub> Adsorbent**  
<sup>1</sup>H. Yoon, <sup>1</sup>K. Mi-Hye, <sup>1</sup>J. Bae, <sup>2</sup>K. Chung  
<sup>1</sup>Korea Basic Science Institute, Korea  
<sup>2</sup>Korea Institute of Geoscience & Mineral Resources, Korea

P1-089A-LN **Synthesis and Characteristics of Functionalized Polymer Films and Its Application to Aligning and Immobilizing DNA Molecules**

<sup>1</sup>H. KIM, <sup>2</sup>I. Bae, <sup>2</sup>S. Cho, <sup>2</sup>J. Boo, <sup>3</sup>B. Lee, <sup>1</sup>B. Hong,

<sup>1</sup>Sungkyunkwan University, Korea

<sup>2</sup>Sungkyunkwan University, Korea

<sup>3</sup>Korea Atomic Energy Research Institute, Korea

P1-090A-LN **Necking Effect of TiO<sub>2</sub> on Electron Mobility of Dye-sensitized Solar Cell**

<sup>1</sup>M. Shin, <sup>1</sup>J. Kim, <sup>2</sup>H. Kim, <sup>1,2</sup>B. Hong

<sup>1</sup>Interdisciplinary graduate school Program for Photovoltaic specialists (IPPs), Korea

<sup>2</sup>Sungkyunkwan University, Korea

P1-091B-LN **Deep-Ultraviolet Emission Si-doped AlGaN Excited by Electron Beam**

<sup>1</sup>H. Miyake, <sup>1</sup>Y. Shimahara, <sup>1</sup>S. Ochiai, <sup>1</sup>K. Hiramatsu, <sup>2</sup>F. Fukuyo, <sup>2</sup>. Okada, <sup>2</sup>H. Takaoka, <sup>2</sup>H. Yoshida

<sup>1</sup>Mie University, Japan

<sup>2</sup>HAMAMATSU PHOTONICS K.K., Japan

P1-092B-LN **An Improvement of Crystal Quality of Group III-Nitride Thin Films on Sapphire by Using In<sub>2</sub>O<sub>3</sub> Under Layer**

<sup>1</sup>Y. Sato, <sup>1</sup>K. Ito, <sup>1</sup>K. Harada, <sup>1</sup>K. Funaki, <sup>1</sup>H. Takemoto, <sup>1</sup>M. Iwaki

<sup>1</sup>Akita University, Japan

P1-093B-LN **Effect of V/III Ratio on the Morphologies of MOCVD Grown InN Nanowall**

<sup>1</sup>M. Kim, <sup>1</sup>D. Moon, <sup>1</sup>J. Park, <sup>5</sup>H. Lim, <sup>5</sup>H. Cheong, <sup>0</sup>Y. Nanishi, <sup>4</sup>G. Yi, <sup>1,3</sup>E. Yoon

<sup>1</sup>Seoul National University, Korea

<sup>2</sup>Ritsumeikan University, Japan

<sup>3</sup>Seoul National University, Korea

<sup>4</sup>Seoul National University, Korea

<sup>5</sup>Sogang University, Korea